

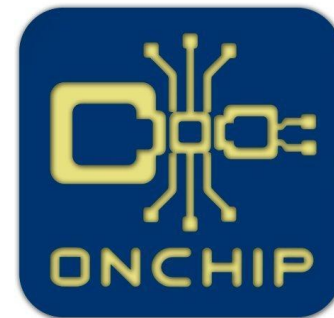
# Lecture 02: Second-order effects on MOSFET & Biasing

**Javier Ardila**

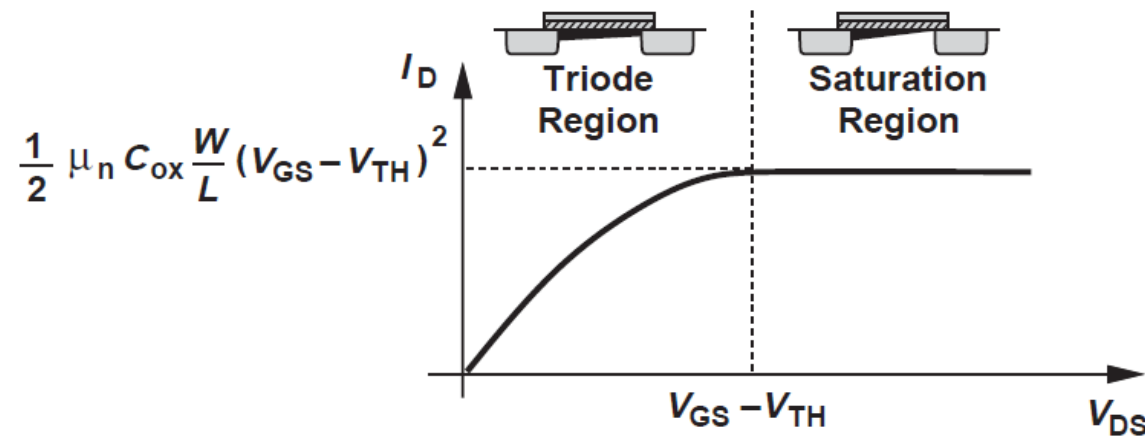
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# Review



TURN ON the Device

$$V_{GS} > V_{TH}$$

## Triode Region

- $V_{DS} < V_{GS} - V_{TH}$
- $I_D$  depends on  $V_{GS}$  and  $V_{DS}$

$$I_D = \mu_n C_{ox} \frac{W}{L} \left[ (V_{GS} - V_{TH}) V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$

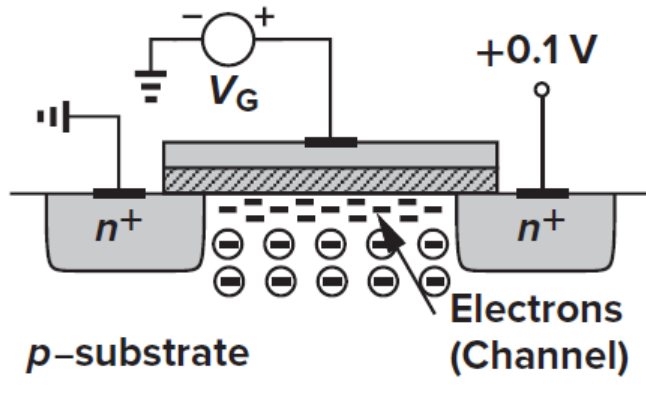
## Saturation Region

- $V_{DS} \geq V_{GS} - V_{TH}$
- $I_D$  depends on  $V_{GS}$  (mostly)

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L_1} (V_{GS} - V_{TH})^2$$

# Body Effect

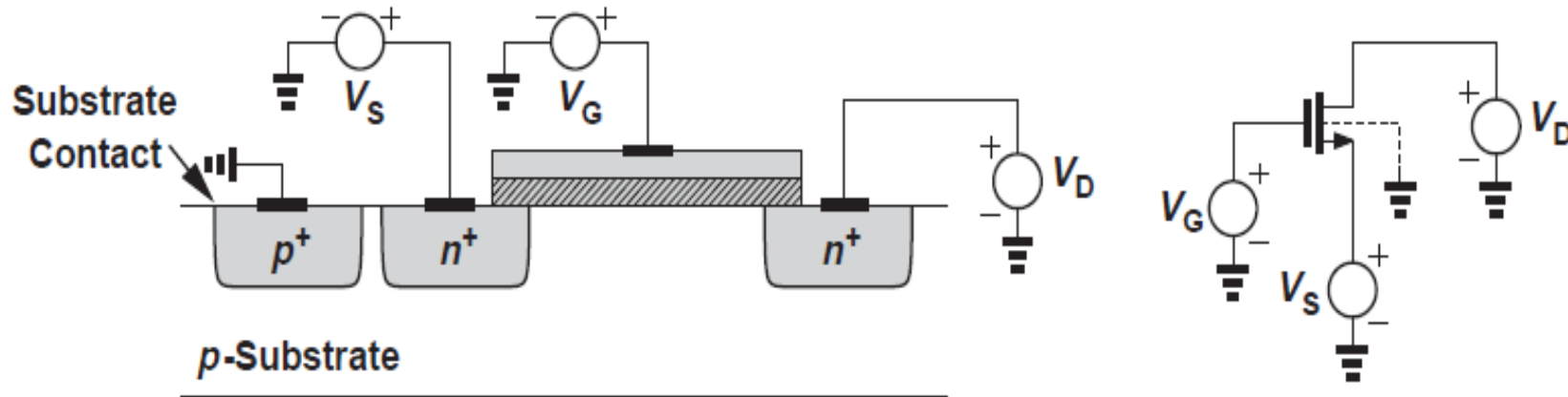
- Remember that a certain value for  $V_{GS}=V_{TH}$  is required to create an inversion layer under the oxide.
- $V_{TH}$  can be considered constant for a given NFET\* if the source and body experiment the same potential.



$$V_{TH} = \Phi_{MS} + 2\Phi_F + \frac{Q_{dep}}{C_{ox}}$$

# Body Effect

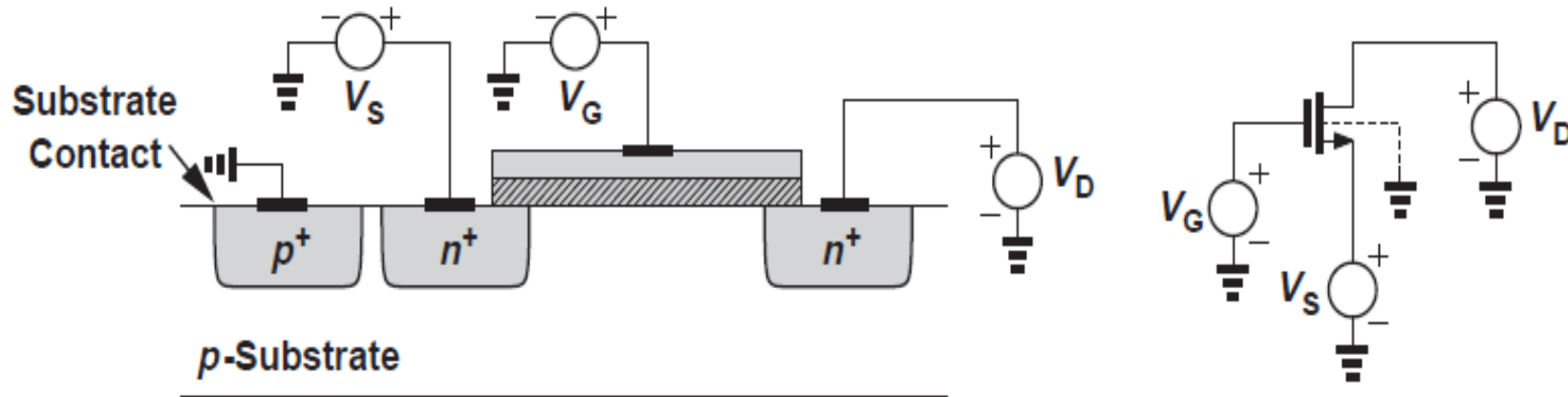
- The body effect appears when source-bulk voltage is different to ZERO ( $\neq 0$ ).



- As the source becomes more positive with respect to the bulk,  $V_{TH}$  increases.

# Body Effect

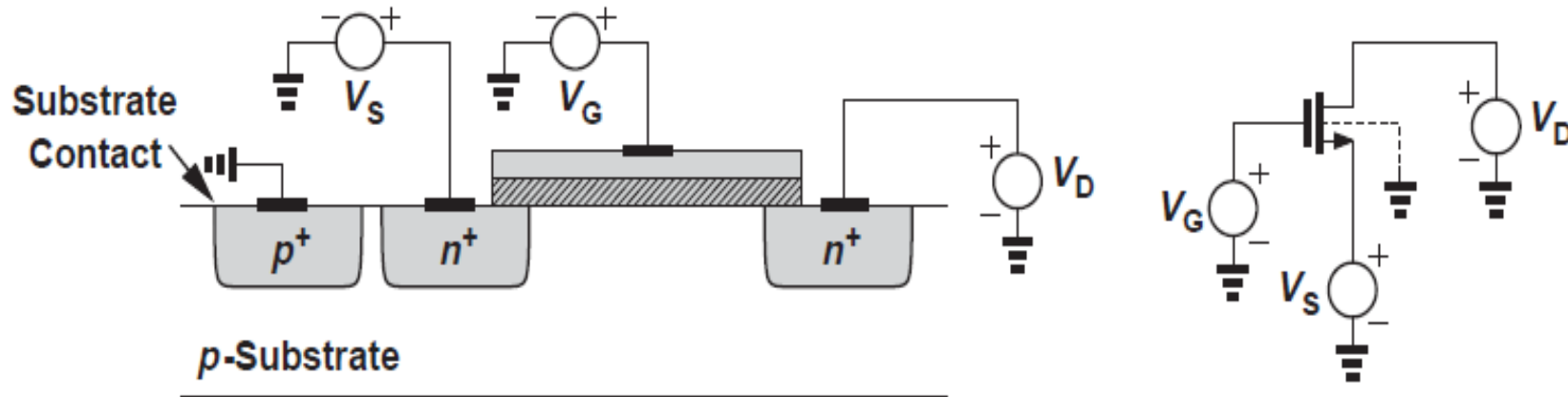
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- As the source becomes more positive with respect to the bulk,  $V_{TH}$  increases. Why?

# Body Effect

- The body effect appears when source-bulk voltage is different to ZERO ( $\neq 0$ ).



- As the source becomes more positive with respect to the bulk, V<sub>TH</sub> increases. Why? **A: Because the depletion region becomes larger**

$$V_{TH} = \Phi_{MS} + 2\Phi_F + \frac{Q_{dep}}{C_{ox}}$$

# Body Effect

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- This phenomenon is called the “body effect” and it can be proved that:

$$V_{TH} = V_{TH0} + \gamma(\sqrt{|2\phi_F + V_{SB}|} - \sqrt{|2\phi_F|})$$

# Body Effect

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$$\Phi_{MS} + 2\Phi_F + \frac{Q_{dep}}{C_{ox}}$$

The “threshold” explained before

(0.3~0.4V<sup>1/2</sup>)

$$\gamma = \sqrt{2q\epsilon_{si}N_{sub}}/C_{ox}$$

body-effect coefficient



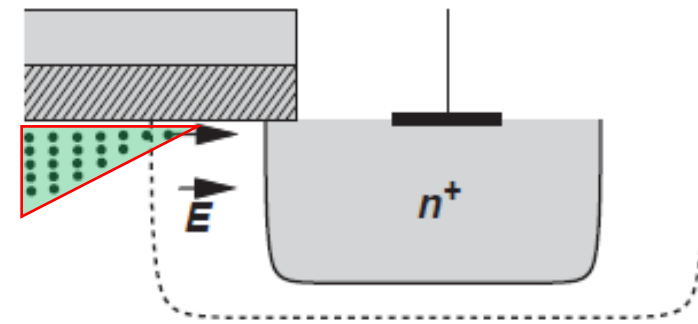
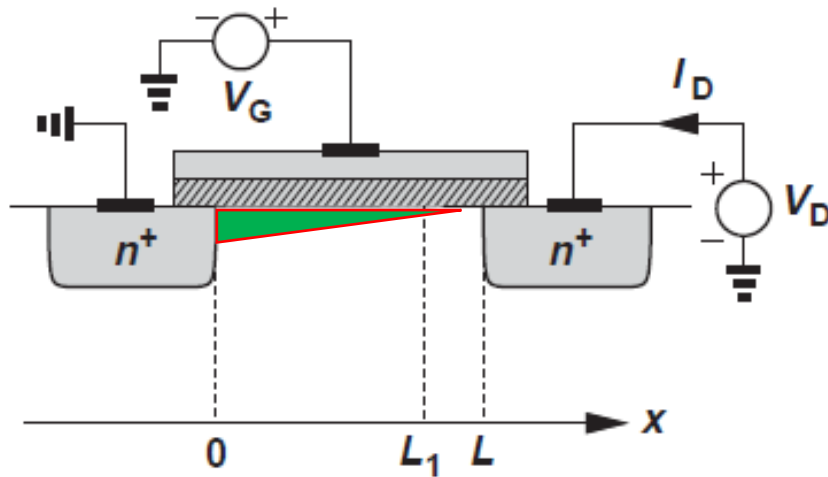
# Channel Length Modulation

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- Remember that:
- If  $V_{DS}=V_{GS}-V_{TH}$  then the channel is pinched-off.
- Actually, for greater values of  $V_{DS}$  the region under the gate without inversion layer extends towards the source.

# Channel Length Modulation

- Remember that:
- If  $V_{DS} = V_{GS} - V_{TH}$  then the channel is pinched-off.
- Actually, for greater values of  $V_{DS}$  the region under the gate without inversion layer extends towards the source.



# Channel Length Modulation

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- Current expression:

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L_1} (V_{GS} - V_{TH})^2$$

- $L_1$  is a function of  $V_{DS}$ . We can write:

$$L_1 = L - \Delta L$$

Assuming that  $L \gg \Delta L$ , then,

$$1/L_1 \approx (1 + \Delta L/L)/L$$

And assuming a first-order relationship between  $\Delta L/L$  and  $V_{DS}$ , such as  
 $\Delta L/L = \lambda V_{DS}$

# Channel Length Modulation

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- Current expression is modified to:

$$I_D \approx \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2 (1 + \lambda V_{DS})$$

# Channel Length Modulation

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Same as before

Additional term

- Now the current has a dependence on VDS and results in a non-ideal current source between source and drain.

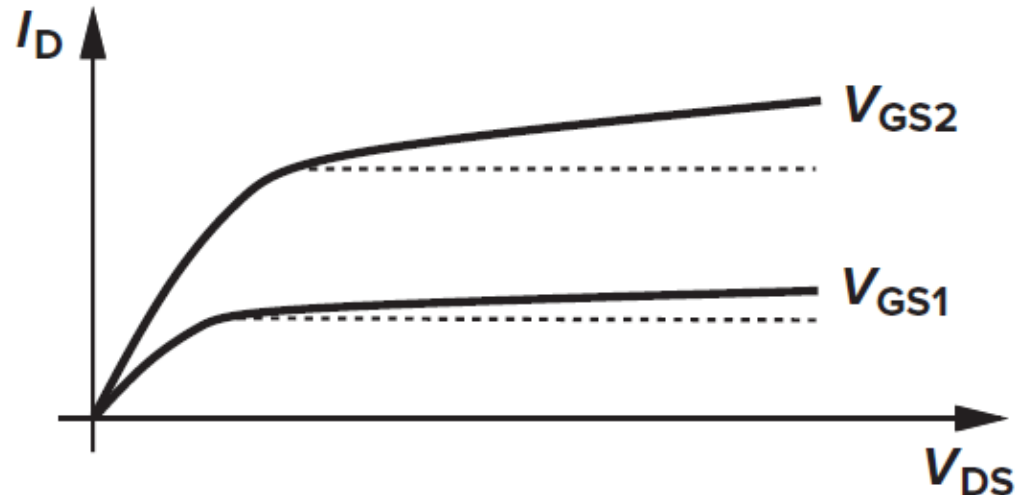
# Channel Length Modulation

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Additional term



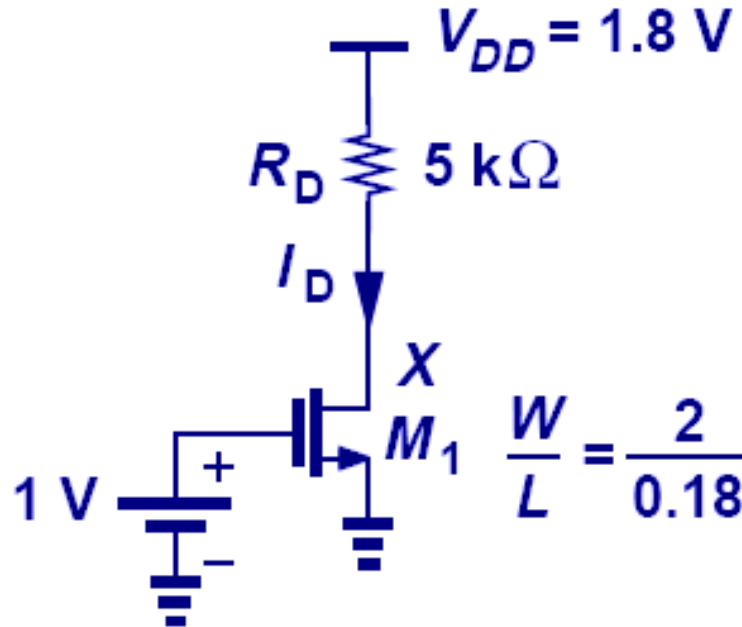
# Exercise for class

**Calculate the bias current of M1.**

**Assume:**

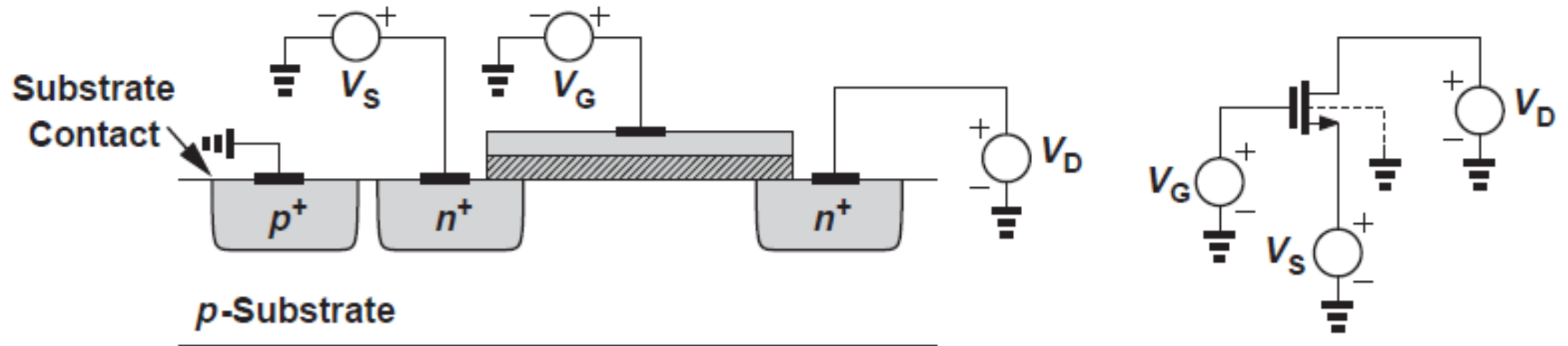
$$\mu_n C_{ox} = 100 \mu\text{A}/\text{V}^2$$

$$V_{TH} = 0.4\text{V}$$



- When the region of operation is not known, a region is assumed (with an intelligent guess). Then, the final answer is checked against the assumption.

# Circuit for exercise





# Additional exercises

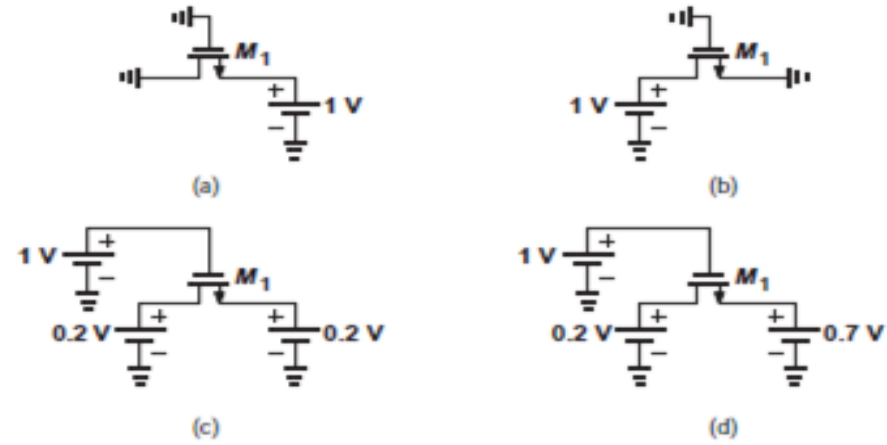


Figure 6.38

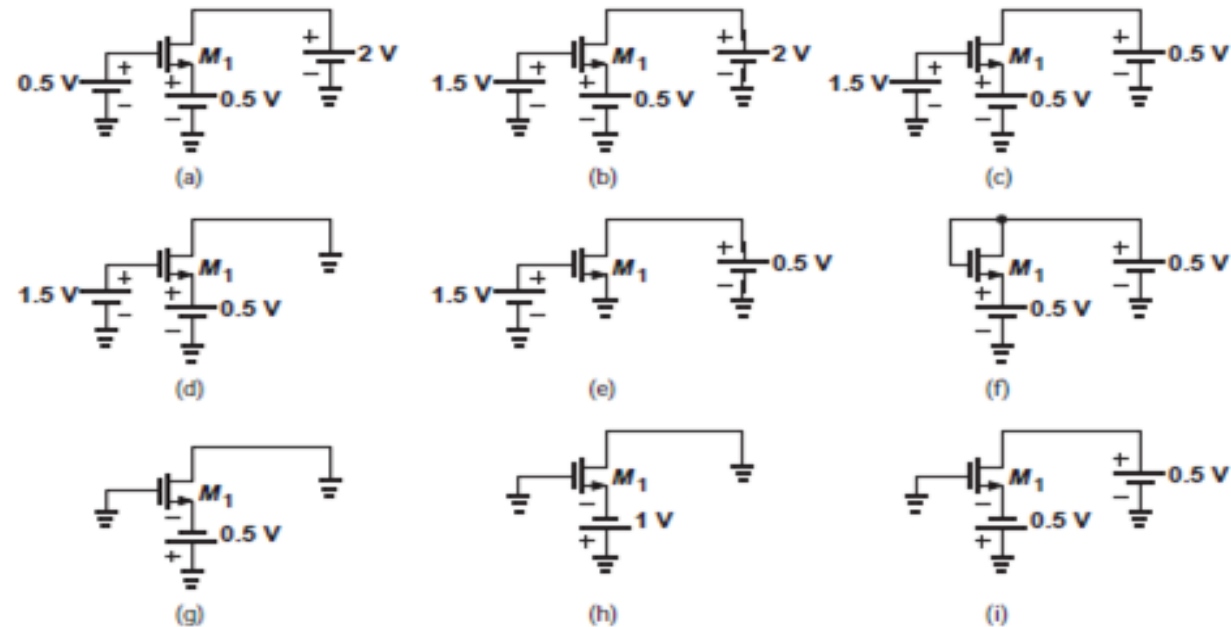
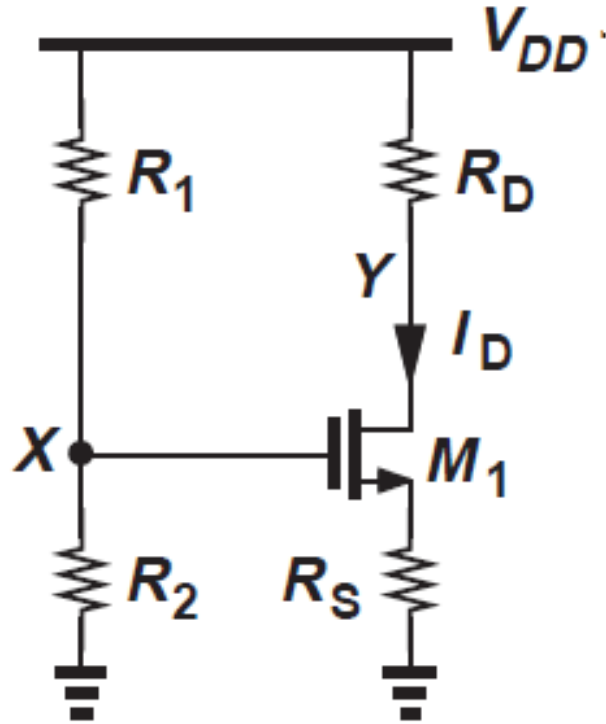


Figure 6.39

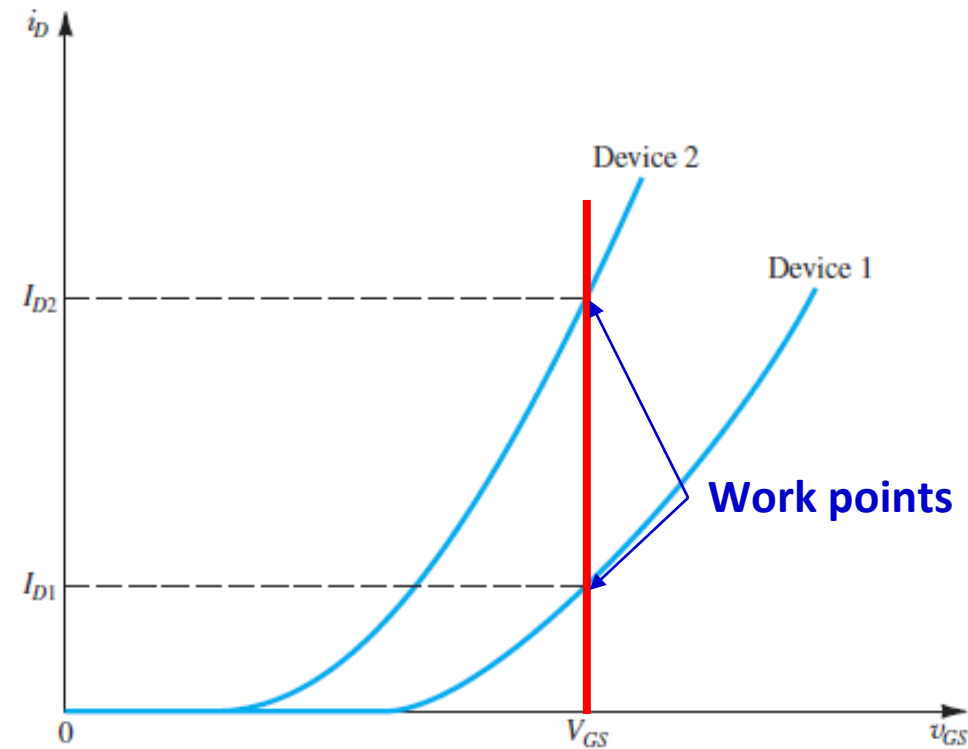
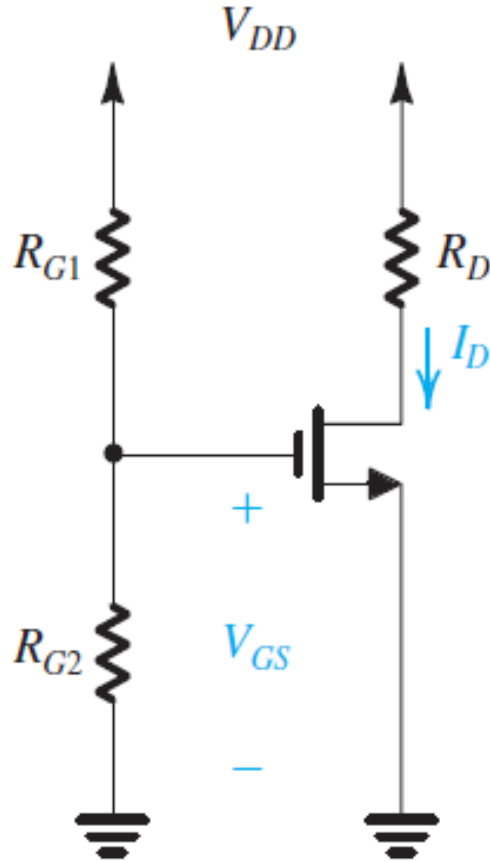
# Biasing in MOS transistor

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- The main idea is to find the “work point” of the transistor.
- Remember to assume a region, do the calculations and then verify the results.

# Biasing by fixing $V_{GS}$



- This is the easiest way to bias the transistor, but it is not a good way

# Review

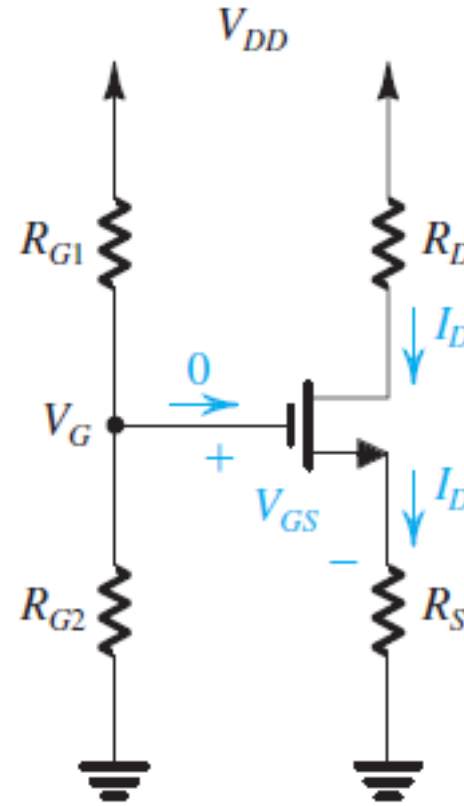
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- Recall that:

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2.$$

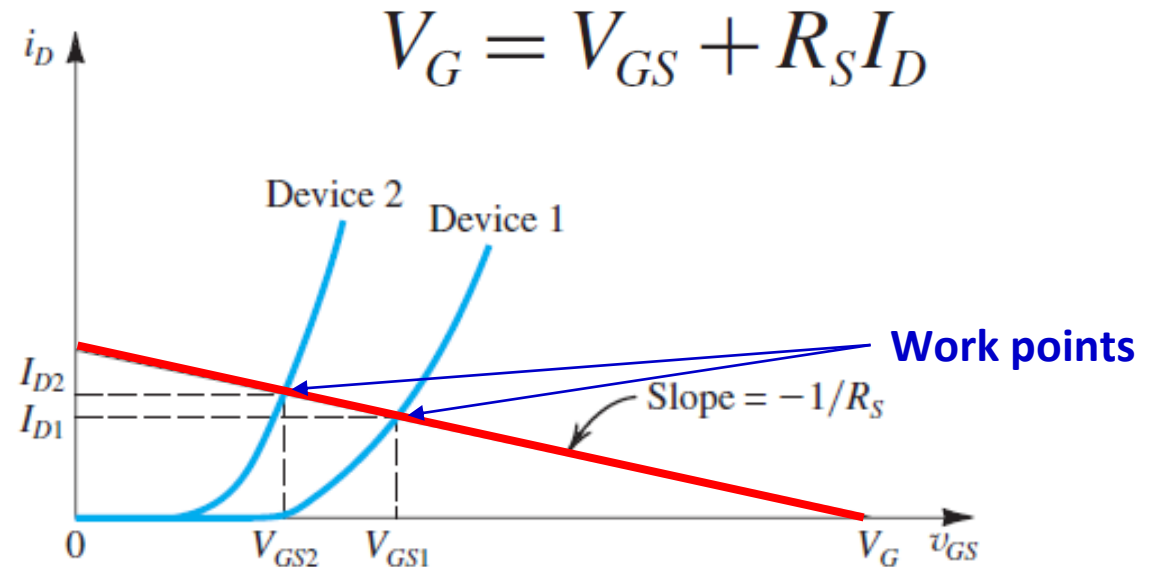
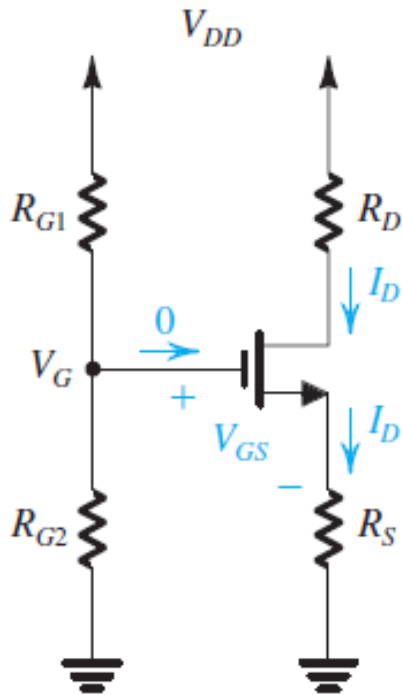
- We fixed the gate-source voltage using a voltage divider. But this has a lot of dependences.
- Check the curves for extreme transistors of the same batch

# Biasing by fixing $V_{GS}$ and $R_S$ resistor



- Connecting an  $R_S$  resistor to the source terminal can help to solve the great dependence of  $I_D$  on MOS parameters.

# Biasing by fixing $V_{GS}$



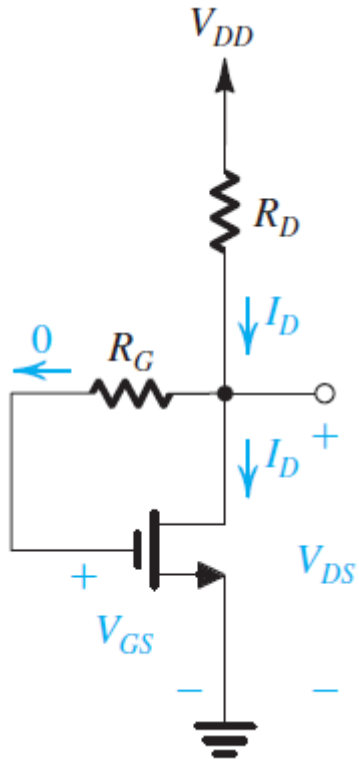
- Here, the variability of  $I_D$  is smaller
- Take care of the valid region of red line!

# Examples

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- Determine the bias current of  $M1$  for the two bias schemes explained before, assuming  $V_{TH} = 0.5V$ ,  $\mu nC_{ox} = 100 \mu A/V^2$ ,  $W/L = 5/0.18$ , and  $\lambda = 0$ . What is the maximum possible value of  $R_D$  for  $M1$  to remain in saturation?.  $R_{G1}=4k$ ,  $R_{G2}=10K$ ,  $R_S=1K$ .

# Self Biasing



$$V_{GS} = V_{DS} = V_{DD} - R_D I_D$$

$$V_{DD} = V_{GS} + R_D I_D$$

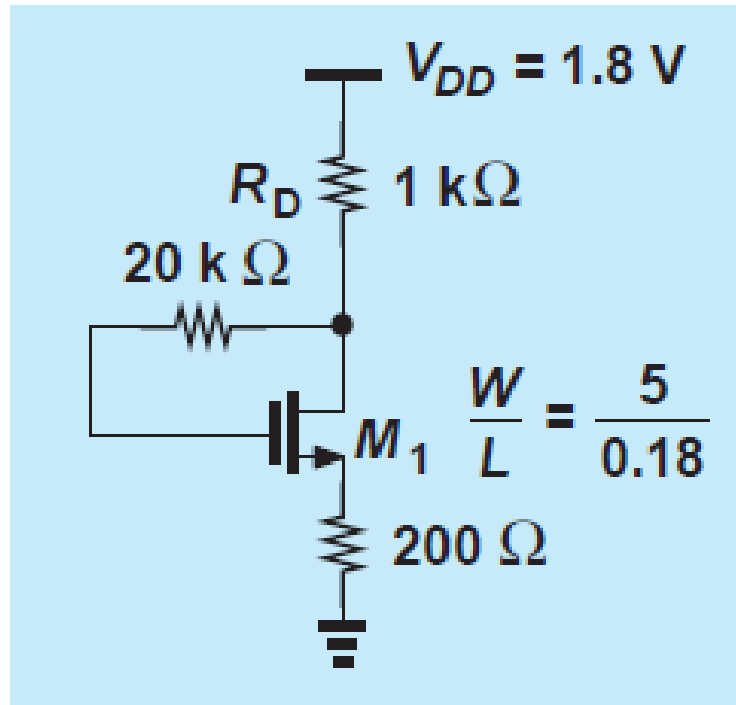
$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2.$$

- What is the operation region of the MOSFET?
- Also it is possible to add an  $R_s$  resistor!



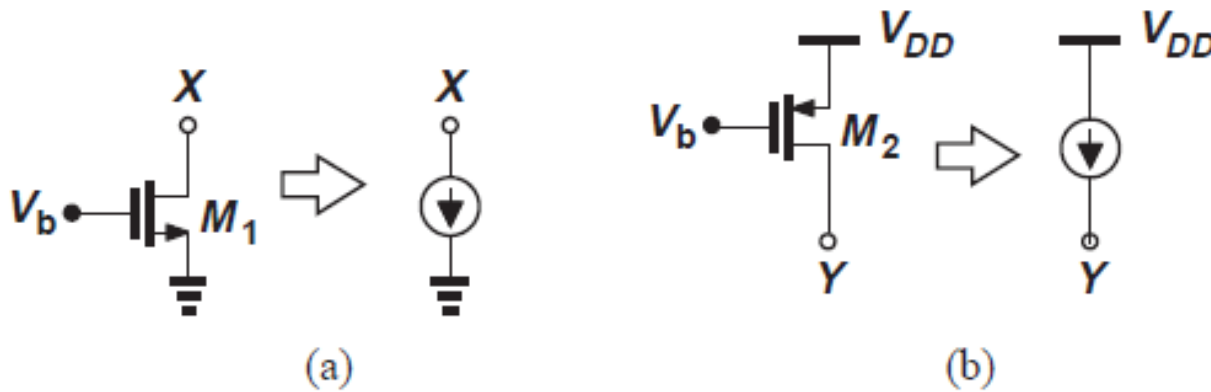
# Examples

- Calculate the drain current of  $M_1$  if  $\mu n C_{ox} = 100 \mu\text{A/V}^2$ ,  $V_{TH} = 0.5 \text{ V}$ , and  $\lambda = 0$ . What value of  $R_D$  is necessary to reduce  $I_D$  by a factor of two?



# Biasing with current source

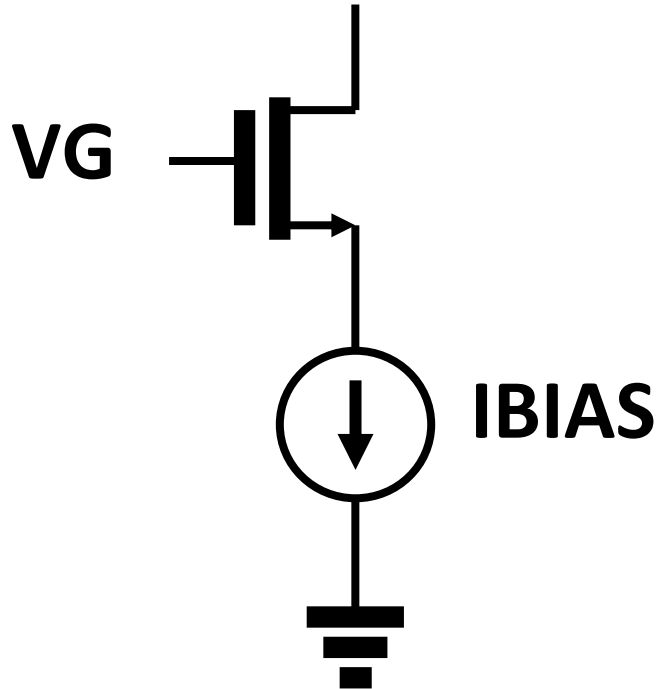
- MOSFETs operating in saturation region may act similar to a current source? Why?
- What are the differences regarding an ideal current source?



- Actually, current sources are implemented with MOS devices!!!

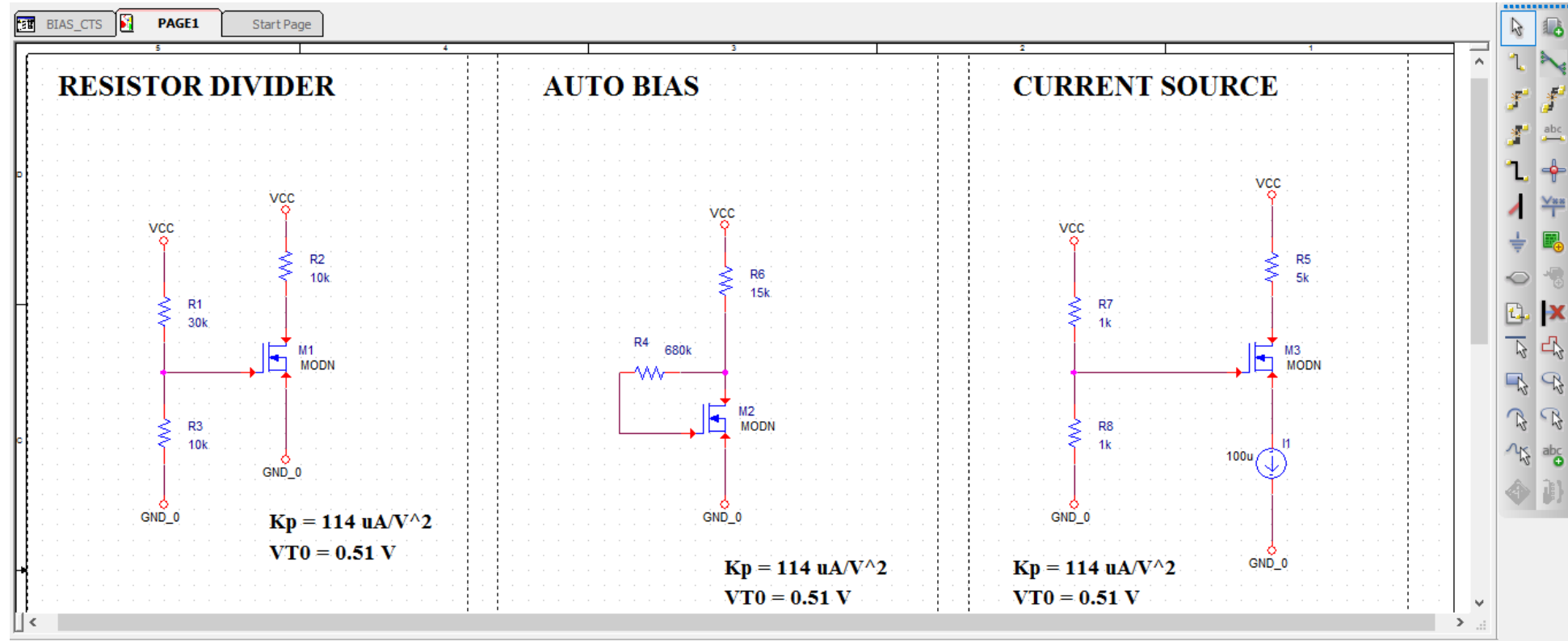
# Biasing with current source

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- Fix the bias point by using a current source
- Fixing  $I_D$  is almost the same as fixing  $V_{GS}$  in saturation region.

# Additional Examples: OrCAD





Thanks!